

**PATENT APPLICATION**  
**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q80214

Tsutomu SHOKI , et al.

Appln. No.: Not yet assigned

Confirmation No.: Not yet assigned

Group Art Unit: Not yet assigned

Filed: March 02, 2003

Examiner: Not yet assigned

For: REFLECTIVE MASK BLANK HAVING A PROGRAMMED DEFECT AND  
METHOD OF PRODUCING THE SAME, REFLECTIVE MASK HAVING A  
PROGRAMMED DEFECT AND METHOD OF PRODUCING THE SAME, AND  
SUBSTRATE FOR USE IN PRODUCING THE REFLECTIVE MASK BLANK OR  
THE REFLECTIVE MASK HAVING A PROGRAMMED DEFECT

**PRELIMINARY AMENDMENT**

**MAIL STOP NON-FEE AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Prior to examination, please amend the above-identified application as follows on the  
accompanying pages.

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